



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. .... 10/783,242  
Filing Date ..... February 19, 2004  
Confirmation No. .... 1437  
Inventor ..... Garo J. Derderian et al.  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 2812  
Examiner ..... Alexander G. Ghyka  
Attorney's Docket No. .... MI22-2403  
Customer No. .... 021567  
Title: Atomic Layer Deposition Method of Forming an Oxide Comprising  
Layer on a Substrate

**RESPONSE TO JUNE 8, 2005 OFFICE ACTION**

To: Mail Stop Amendment  
Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

**VIA U.S. EXPRESS MAIL**

From: Mark Matkin (Tel. 509-624-4276; Fax 509-838-3424)  
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Responsive to the Office Action dated June 8, 2005, Applicant amends  
and remarks as follows:

**AMENDMENTS**

**EV633262615**